

GANPAT UNIVERSITY

B. Tech. Semester VII Electronics and Communication Engineering

Regular Examination NOV/DEC-2012

EC 703 VLSI Technology

Time: 3 Hrs.]

[Total. Marks: 70

Instructions:

1. Attempt all questions.
2. Answers to the two sections must be written in separate answer books.
3. Figures to the right indicate full marks.
4. use following data.

$$\Phi_{F(\text{gate})} = 0.55\text{V}, \quad kT/q = 0.026\text{V}, \quad q = 1.6 \times 10^{-19}\text{C}, \quad \epsilon_0 = 8.85 \times 10^{-14}\text{F/cm},$$

$$\epsilon_{\text{Si}} = 11.7 \times \epsilon_0\text{F/cm}, \quad \epsilon_{\text{ox}} = 3.7 \times \epsilon_0\text{F/cm}, \quad n_i = 1.45 \times 10^{10}/\text{cm}^3$$

SECTION-I

- 1 (A) Explain Gradual Channel Approximation (GCA) and derive equation for drain current I_D (lin) and I_D (sat). 6
- (B) Explain following processes for the MOS system with necessary diagram: 6
 1. Accumulation 2. Depletion 3. Inversion

OR

- 1 (A) Write a short note on MOSFET capacitance 6
- (B) Draw the following CMOS based circuit : 6
 1. CMOS implementation of the D-Latch
 2. CMOS AOI realization of the JK latch
- 2 (A) Give the types of voltage scaling and its effects on different parameters 6
- (B) Draw the CMOS negative edge-triggered master slave D FF 5

OR

- 2 (A) Implement $(A+B)C$ using cascade domino CMOS logic 3
- (B) Draw the following digital circuit using transmission gate 8
 1. 2:1 MUX
 2. 4:1 MUX
 3. 2 input EX-OR gate
 4. $F = AB + A'C' + AB'C$
- 3 (A) Design 4 input NAND Gate using pass transistor 6
- (B) What is latch up? Explain Causes of latch-up & how to avoid it. 6

SECTION-II

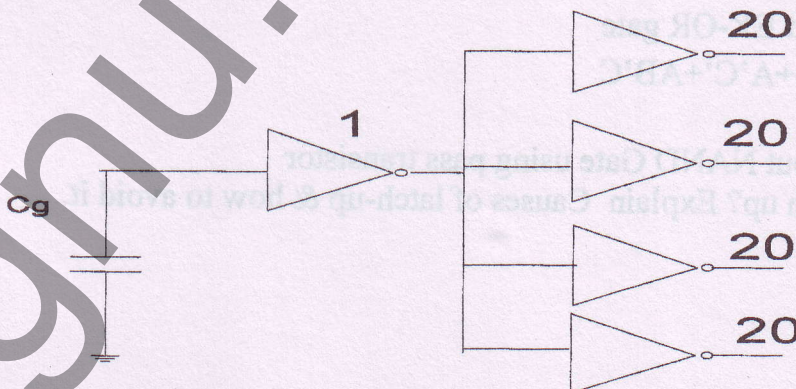
- 4 (A) Explain CMOS ring oscillator circuit for three stages 6
 (B) Calculate the threshold voltage V_{TO} at $V_{SB}=0$, for a polysilicon gate n-channel MOS transistor, with the following parameter: Substrate doping density $N_A=10^{16} \text{ cm}^{-3}$ polysilicon gate doping density $N_D = 2 \times 10^{20} \text{ cm}^{-3}$, gate oxide thickness $t_{ox}=500\text{\AA}$, and oxide-interface fixed charge density $NOX = 4 \times 10^{10} \text{ cm}^{-2}$ 6

OR

- 4 (A) Give comparison of different inverter with necessary diagram. 4
 (B) Explain channel length modulation effects in NMOS. 4
 (C) Write a short note on voltage bootstrapping 4
- 5 (A) What is inverter threshold voltage? Explain its effect & derive the equation $\left(\frac{W}{L}\right)_p = 2.5\left(\frac{W}{L}\right)_n$ 6
 (B) Draw circuit diagram of 3T DRAM cell with its working and related voltage waveforms. 5

OR

- 5 (A) Define τ_{PHL} & τ_{PLH} . Derive the equation for delay time(t_d) and explain its effect 4
 (B) Draw the following digital circuit using transmission gate 4:1 MUX using 2:1 MUX 4
 (C) Write a short note on LOCOS 3
- 6 (A) Optimize stick diagram layout of a complex CMOS logic gate for $Y=((A+B+C)D)'$ using Euler path method 6
 (B) For given below circuit, if $t_{po}=0.5\text{ns}$ then find delay for
 (a) Non buffer case
 (b) Single buffer case
 (c) Super buffer case 6

End of Paper